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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/867,464	05/31/2001	Takahisa Kikuchi	209294US-2	6875
22850	7590 11/18/2002			
OBLON SPIVAK MCCLELLAND MAIER & NEUSTADT PC FOURTH FLOOR 1755 JEFFERSON DAVIS HIGHWAY			EXAMINER	
			LAU, TUNG S	
ARLINGTON	ARLINGTON, VA 22202		ART UNIT	PAPER NUMBER
			2863	
			DATE MAILED, 11/19/2002	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)
,		09/867,464	KIKUCHI, TAKAHISA
pai	Office Action Summary	Examiner	Art Unit
		Tung S Lau	2863
·	The MAILING DATE of this commun	ication appears on the cover sheet	with the correspondence address
eriod for	Reply		•
THE W - Extens after S - If the p - If NO	ORTENED STATUTORY PERIOD F IAILING DATE OF THIS COMMUNI sions of time may be available under the provisions SIX (6) MONTHS from the mailing date of this commoderiod for reply specified above is less than thirty (3 period for reply is specified above, the maximum st e to reply within the set or extended period for reply sply received by the Office later than three months a d patent term adjustment. See 37 CFR 1.704(b).	s of 37 CFR 1.136(a). In no event, however, may nunication. 30) days, a reply within the statutory minimum of the latutory period will apply and will expire SIX (6).	a reply be timely filed thirty (30) days will be considered timely. ONTHS from the mailing date of this communication.
1) <u> </u>	Responsive to communication(s) fi	iled on <u>21 October 2002</u> .	
2a)□	This action is FINAL	2b)⊠ This action is non-final.	
3)	Since this application is in conditio closed in accordance with the practice.	n for allowance except for formal natice under Ex parte Quayle, 1935	natters, prosecution as to the merits is C.D. 11, 453 O.G. 213.
	on of Claims		•
4)🖂	Claim(s) 1-39 is/are pending in the	application.	
,	4a) Of the above claim(s) is/a	are withdrawn from consideration.	
5)🖂	Claim(s) 35-37 is/are allowed.		
6)⊠	Claim(s) <u>1-5,7-9,13,16,17,19,22,25</u>	<u>i,31,38 and 39</u> is/are rejected.	
7)🖂	Claim(s) 6,10-12,14,15,17,18,20,2	<u>1,23,24,26-30 and 32-34</u> is/are obj	ected to.
8)[Claim(s) are subject to restr	iction and/or election requirement.	
	ion Papers	_	
9)	The specification is objected to by t	he Examiner.	by the Evaminer
10)	The drawing(s) filed on is/are	e: a) accepted or b) objected to	bevance See 37 CFR 1.85(a).
	Applicant may not request that any o The proposed drawing correction fil	bjection to the drawing(s) be held in a	disapproved by the Examiner.
11)	The proposed drawing correction file	ed on is. a) approved b)	
	If approved, corrected drawings are	required in reply to this Office action.	
	The oath or declaration is objected	to by the Examiner.	
Priority	under 35 U.S.C. §§ 119 and 120		: C & 119(a)-(d) or (f)
	Acknowledgment is made of a claim		(d) 31 (d) (d) (d)
a) ☐ All b) ☐ Some * c) ☐ None of	i.	·
	1. Certified copies of the priori	ty documents have been received	in Application No
	2. Certified copies of the priori	ity documents have been received	accer received in this National Stage
*	application from the Inte	ernational Bureau (PC) Rule 17.2(tion for a list of the certified copies	filot received.
14)[]	Acknowledgment is made of a claim	n for domestic priority under 35 U.	S.C. § 119(e) (to a provisional application)
	a) The translation of the foreign Acknowledgment is made of a clair a)	language provisional application h	as been received.
Attachme		:	
1) 🔯 No	tice of References Cited (PTO-892) tice of Draftsperson's Patent Drawing Revieu		rview Summary (PTO-413) Paper No(s) ice of Informal Patent Application (PTO-152)

Art Unit: 2863

DETAILED ACTION

Response to election/restriction

Applicant's election with traverse of 10-21-2002 in Paper No. 8 is acknowledged.
 The arguments is found persuasive and the examiner withdraw the restriction requirement.

Claim Rejections - 35 USC § 102

- The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:
 A person shall be entitled to a patent unless
 - (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1, 2, 3, 4, 19, 39 are rejected under 35 U.S.C. 102(b) as being anticipated by Sato et al (U.S. Patent 5,499,099).

Sato discloses a method that evaluates a substrate and alignment mode by obtaining a plurality of divided areas on a substrate, position deviation amount with reference position by a marks, (abstract, col. 3-4, lines 35- 4, fig 6a, 6b), evaluating a nonlinear distortion of the substrate to obtain correlation direction of an given area with the second substrate represent the position deviation of the divided area (col. 5-6, lines 27-36), grouping plurality of substrates of a nonlinear distortion of the substrate earlier to determine position information of the divided area (col. 4, lines 50—6, lines 50-67, col. 7-9, lines 60-8) relative position information with position deviation of the divide areas where the second number

Art Unit: 2863

is smaller than the first number (col. 8, lines 37-67), using addition to evaluate function to determine position information, N functions of divide area (col. 6, lines 1-6), using coordinate system, having linear component to calculate position information (col. 6, lines 16-37), n substrate where n is larger or equal to two (col. 6, lines 15-50).

Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
 - a. Claims 5, 7, 8, 9, 13, 16, 17, 22, 31, 38 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sato et al (U.S. Patent 5,499,099) in view of Irie et al. (U.S. Patent 5,808,910).

Sato discloses a method including the subject matter discussed above except the use of statistic computation, with three specific areas of samples, with weight parameter. Irie discloses the use of statistic computation (col. 3-4, lines 25-22), three specific areas of samples (col. 4, lines 23-53), with weight parameter (col. 15-16, lines 25-40), to have a high accuracy and high speed even though a sample has a nonlinear error (col. 3, lines 19-23).

Art Unit: 2863

It would have been obvious to one of ordinary skill in the art at the time the invention was made to modify Sato to have the use of statistic computation, with three specific areas of samples, with weight parameter taught by Irie in order to have a high accuracy and high speed alignment system even though a sample has a nonlinear error.

b. Claim 25 are rejected under 35 U.S.C. 103(a) as being unpatentable over the combination of Sato and Irie as applied to claims 1, 19, 22, and further in view of Tomimatu (U.S. Patent 6,239,858).

The Sato and Irie combination disclose a method including the subject matter discussed above except the use of correction map technique. Tomimatu discloses the use of correction map technique (col. 1, lines 60-64), to reduce nonlinear error generated from semiconductor substrate (col. 2, lines 21-28).

It would have been obvious to one of ordinary skill in the art at the time the invention was made to modify Sato and Irie to have the use of correction map technique taught by Tomimatu in order to reduce nonlinear error generated from semiconductor substrate.

Art Unit: 2863

Allowabl Subject Matter

- 4. Claims 35-37 are allowed.
- 5. Claims 6, 10, 11, 12, 14, 15, 17, 18, 20, 21, 23, 24, 26-30, 32-34 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- 6. The following is an examiner's statement of reasons for allowance:

Regarding claim 35:

The prior art of record does not disclose or suggest the claimed combination of overlay analysis step of analyzing overlay error information, measured beforehand, of at least one specific substrate that has been through the same process as the substrates.

A first judgment step of judging, based on the analysis results, whether or not errors between divided areas on said specific substrate are predominant, the errors between divided areas being caused by position deviation amounts having different translation components from each other;

A second judgment step of, when in the first judgment step it has been judged that said errors between divided areas are predominant, judging whether or not the errors between divided areas have a nonlinear component;

Art Unit: 2863

A first exposure step of, when in said second judgment step it has been judged that the errors between divided areas have no nonlinear component, with using an arbitrary exposure apparatus.

Calculating pieces of position information used to align each divided area with respect to a predetermined point, by a statistic computation using measured position information obtained by detecting marks corresponding to each of a plurality of specific divided areas on each of said plurality of substrates and sequentially performing exposure on said plurality of divided areas of each of the plurality of substrates so as to form the pattern on each divided area, while moving said substrate based on the pieces of position information; a second exposure step of, when in the second judgment step it has been judged that the errors between divided areas have a nonlinear component, with using an exposure apparatus that can perform exposure on substrates correcting the errors between divided areas, sequentially performing exposure on said plurality of divided areas of each of the plurality of substrates so as to form said pattern on each divided area; and a third exposure step of, when in the first judgment step it has been judged that errors between divided areas are not predominant, selecting an exposure apparatus capable of correcting distortion of the projected image and, with using selected exposure apparatus, sequentially performing exposure on plurality of divided areas of each of plurality of substrates so as to form pattern on each divided area.

Claims 36, 37 are allowed due to their dependency on claim 35.

Art Unit: 2863

7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Tung S Lau whose telephone number is 703-305-3309.

The examiner can normally be reached on M-F 9-5:30.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, John Barlow can be reached on 703-308-3126. The fax phone numbers for the organization where this application or proceeding is assigned are 703-308-5841 for regular communications and 703-308-5841 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

TC2800 RightFAX Telephone Numbers: TC2800 Official Before-Final RightFAX - (703) 872-9318, TC2800 Official After-Final RightFAX - (703) 872-9319

TC2800 Customer Service RightFAX - (703) 872-9317

TL

BRYAN BUI PRIMARY EXAMINER

1-13-102